

10/564447

AP20 REGISTRATION 12 JAN 2006

**THE FOLLOWING ARE THE ENGLISH TRANSLATION
OF ANNEXES TO THE INTERNATIONAL PRELIMINARY
EXAMINATION REPORT (ARTICLE 34):**

Amended Sheets (Pages 21-23)

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(Claims after Amendment)

CLAIMS

1. (Amended) A probe for a scanning probe microscope, comprising:

- (a) a base of the probe of the probe microscope; and
- (b) a support cantilever extending horizontally from the base, a top end of the support cantilever being processed to have a sloped surface so as not to prevent a measuring cantilever from being optically observed;

wherein the measuring cantilever is provided on the top end of the support cantilever and the measuring cantilever has a length less than or equal to 20 micrometers and a thickness less than or equal to 1 micrometer.

2. The probe for a scanning probe microscope according to Claim 1, wherein the base and the support cantilever are formed from a single-crystal silicon and the measuring cantilever is formed from a single-crystal silicon thin film, and wherein the measuring cantilever is coupled with the top end of the support cantilever.

3. (canceled)

4. The probe for a scanning probe microscope according to Claim 1, wherein the length of the measuring cantilever is

precisely defined by reducing the thickness of the measuring cantilever to less than the thickness of a coupling portion between the measuring cantilever and the support cantilever.

5. The probe for a scanning probe microscope according to Claim 1, wherein the length of the measuring cantilever is precisely defined by reducing the width of the measuring cantilever to less than the width of a coupling portion between the measuring cantilever and the support cantilever.

6. A method for fabricating the probe for a scanning probe microscope according to Claim 2, comprising:

fabricating the base and the support cantilever by processing a single-crystal silicon substrate;

fabricating the measuring cantilever by processing a single-crystal silicon thin film of an SOI substrate different from the single-crystal silicon substrate;

bonding the measuring cantilever with the support cantilever; and

removing a handling wafer and an embedded oxide film of the SOI substrate.

7. The method for fabricating the probe for a scanning probe microscope according to Claim 6, further comprising:

forming a probe tip on the top end of the measuring

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cantilever by means of wet etching.